

ABSTRACT OF THE DISCLOSURE

A vapor deposition production system for coating substrates is provided which includes a plurality of vapor deposition coaters, a plurality of platters, a platter docking station, a shuttle track, and apparatus for transporting the platters between the coaters and the platter docking station. The shuttle track connects the platter docking station and the coaters. Platters selectively removed from the coaters are transported along the shuttle track to the platter docking station where processed substrates are unloaded from the platters and unprocessed substrates loaded on to the platters.